

IN THE CLAIMS

Please amend the claims as follows:

4. (Amended) The process chamber airflow system as claimed in claim 3, wherein the air diffuser eliminates initial airflow turbulence entering the plenum from an air filter.

6. (Amended) The process chamber airflow system as claimed in claim 5, wherein individual holes, included in the plurality of holes, have varying cross-sectional areas.

7. (Amended) The process chamber airflow system of claim 1, wherein the air diffuser is formed of static charge dissipating material.

9. (Amended) The process chamber airflow system of claim 1, wherein the air diffuser is disposed on one side of a generally cubic chamber of a semiconductor production device.

11. (Amended) The process chamber airflow system of claim 1, wherein the air diffuser diffuses air such that contaminate particles are removed from the chamber by the chamber airflow.

17. (Amended) The process chamber airflow system as claimed in claim 13, wherein [an] individual holes, included in the plurality of holes, have varying cross-sectional areas.

18. (Amended) The air diffuser of claim 13, wherein the plate is formed of static charge dissipating material.

19. (Amended) The air diffuser of claim 13, wherein the air diffuser diffuses air with a substantially laminar flow.

Sub C1

21. (Amended) A method of providing substantially laminar airflow in a process chamber, comprising:

generating an initial flow of air with an initial cross-sectional area;

disposing an air diffuser with a plurality of uniformly spaced hole in the airflow, wherein a total cross-sectional area of the plurality of holes is less then the initial cross-sectional area;

creating a back-pressure of air due to the reduction in the cross-sectional area through the plurality of holes;

dispersing a portion of the initial airflow uniformly across the air diffuser; and

providing uniform airflow through the plurality of holes included in the air diffuser, to the process chamber.

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24. (Amended) The process chamber airflow system of claim 22, wherein the air diffuser is formed of static charge dissipating material.

25. (Amended) The process chamber airflow system of claim 22, wherein the air diffuser diffuses air, such that contaminate particles are removed from the chamber by the chamber airflow.